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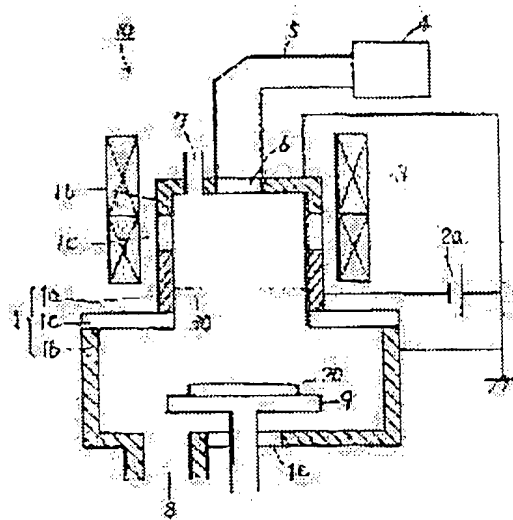
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(54) PLASMA PROCESSING APPARATUS

(57)Abstract:

PURPOSE: To enhance uniformity of etching and anisotropy by eliminating uniformity of distribution of plasma potential, electron density, and ion density.

CONSTITUTION: An electromagnetic coil 3 and a microwave generating source 4 provided so as to generate a magnetic field inside a reaction container 1 and to introduce microwaves into it to make an ECR discharge take place in reactive gas inside the reaction container 1. A specimen pad 9, on which a wafer 20 is placed so as to be etched by plasma generated inside the container 1, is provided inside the container 1. The reaction contain 1 is provided with a first part 1a and second parts 1b insulated from the first part 1a by insulating parts 1c. A potential difference is given between the first part 1a and the second part 1b by a power source 2a.



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